

ABSTRACT

A stage device suitable for exposure apparatus used to produce semiconductor devices, is movable in an area wider than the measurement area of interferometer for position measurement, and is capable of measuring the position with high precision. When a movable stage moves from the position where the laser beams from laser interferometers are not applied into the measurement area of the laser interferometer, the position of reference mark is measured by a wafer alignment sensor, and the measurement value measured by the laser interferometer is corrected based on the results of the measurement by the wafer alignment sensor. When another movable stage enters the measurement area of the laser interferometer, the position of the reference mark is similarly measured by a wafer alignment sensor, and the measurement value measured by the laser interferometer is corrected based on the results of the measurement by the wafer alignment sensor.

005750-00000000